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This listing of claims will replace all prior versions of claims in the application.

Claims 1-10. (cancelled)

Claim 11. (new) A photoimageable composition comprising a photoactive component and a polymer component,

the polymer component comprising a fluorinated polymer that comprises Si atoms and silanol groups,

wherein the polymer: (i) photoacid-labile groups; (ii) comprises at least three distinct repeat units; (iii) is at least substantially free of aromatic groups; and (iv) has a ratio of fluorine atoms to Si atoms of 2.9 or less.

- Claim 12. (new). The photoimageable composition of claim 11 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2.5 or less.
- Claim 13. (new). The photoimageable composition of claim 11 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2 or less.
- Claim 14. (new). The photoimageable composition of claim 11 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2.9 to 2.
- Claim 15. (new) The photoimageable composition of claim 11 wherein at least two of the distinct repeat units have differing numbers of fluorine atoms.
- Claim 16. (new) The photoimageable composition of claim 11 wherein at least two of the distinct repeat units have differing numbers of silicon atoms.

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Claim 17. (new) A coated substrate comprising:

- a) a polymer composition coating layer applied over a substrate surface;
- b) a coating layer of a photoimageable composition of claim 11 disposed over the polymer composition coating layer.
 - Claim 18. (new) A method for forming a electronic device, comprising:
 - (a) applying on a substrate a coating layer of an organic polymer composition;
- (b) over the polymer composition coating layer, applying a photoimageable composition of claim 11;
- (c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.
- Claim 19. (new) The method of claim 18 wherein the photoimageable composition is exposed to radiation having a wavelength of 193 nm.
- Claim 20. (new). The method of claim 18 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2.5 or less.
- Claim 21. (new). The method of claim 18 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2 or less.
- Claim 22. (new). The method of claim 18 wherein the polymer has a ratio of fluorine atoms to silicon atoms of about 2.9 to 2.